

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	430	(427/237).CCLS.	US-PGPUB; USPAT	OR	OFF	2005/02/24 09:53
L2	2	L1 and ((ALE or ALD or (atomic adj layer adj (deposit\$3 or epitax\$5))))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/02/24 10:24
L3	0	L1 and (alternat\$5 near3 sequential\$4)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/02/24 09:56
L4	12	L1 and (puls\$5 near3 (vapor or gas or reactant or reagent or precursor))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/02/24 09:56
L5	3716	(427/248.1,255.23,255.28,255.7,587).CCLS.	US-PGPUB; USPAT; USOCR	OR	OFF	2005/02/24 09:57
L6	6906	(118/715,719,724,725,728).CCLS.	US-PGPUB; USPAT; USOCR	OR	OFF	2005/02/24 09:58
L7	1616	(117/84,85,88,105,200,201).CCLS.	US-PGPUB; USPAT; USOCR	OR	OFF	2005/02/24 09:58
L8	10689	((427/248.1,255.23,255.28,255.7,587).CCLS.) ((118/715,719,724,725,728).CCLS.) ((117/84,85,88,105,200,201).CCLS.)	US-PGPUB; USPAT	OR	ON	2005/02/24 09:58
L9	11	(((427/248.1,255.23,255.28,255.7,587).CCLS.) ((118/715,719,724,725,728).CCLS.) ((117/84,85,88,105,200,201).CCLS.)) and ((ALE or ALD or (atomic adj layer adj (deposit\$3 or epitax\$6))) near4 wall)	US-PGPUB; USPAT	OR	ON	2005/02/24 09:58
L10	17	(((427/248.1,255.23,255.28,255.7,587).CCLS.) ((118/715,719,724,725,728).CCLS.) ((117/84,85,88,105,200,201).CCLS.)) and ((ALE or ALD or (atomic adj layer adj (deposit\$3 or epitax\$6))) near6 wall)	US-PGPUB; USPAT	OR	ON	2005/02/24 10:03
L11	6	L10 not L9	US-PGPUB; USPAT	OR	ON	2005/02/24 10:03

L12	48	(((427/248.1,255.23,255.28,255.7,587).CCLS.) ((118/715,719,724,725,728).CCLS.) ((117/84,85,88,105,200,201).CCLS.)) and (ALE or ALD or (atomic adj layer adj (deposit\$3 or epitax\$6))) and ((heat\$3 or temperature) near3 wall) and ((heat\$3 or temperature) near3 (support or susceptor or substrate or base or wafer)))	US-PGPUB; USPAT	OR	ON	2005/02/24 10:05
L13	94	(((427/248.1,255.23,255.28,255.7,587).CCLS.) ((118/715,719,724,725,728).CCLS.) ((117/84,85,88,105,200,201).CCLS.)) and (ALE or ALD or (atomic adj layer adj (deposit\$3 or epitax\$6))) and ((deposit\$3 or decompos\$5 or condens\$5 or contaminat\$4 or coat\$3) near3 (minimiz\$5 or eliminat\$3 or prevent\$3 or avoid\$5) with (chamber or vessel or reactor or wall)))	US-PGPUB; USPAT	OR	ON	2005/02/24 10:15
L15	28	(((427/248.1,255.23,255.28,255.7,587).CCLS.) ((118/715,719,724,725,728).CCLS.) ((117/84,85,88,105,200,201).CCLS.)) and ((ALE or ALD or (atomic adj layer adj (deposit\$3 or epitax\$6))) same ((deposit\$3 or decompos\$5 or condens\$5 or contaminat\$4 or coat\$3) near3 (minimiz\$5 or eliminat\$3 or prevent\$3 or avoid\$5) with (chamber or vessel or reactor or wall)))	US-PGPUB; USPAT	OR	ON	2005/02/24 10:20
L16	37	(((427/248.1,255.23,255.28,255.7,587).CCLS.) ((118/715,719,724,725,728).CCLS.) ((117/84,85,88,105,200,201).CCLS.)) and ((ALE or ALD or (atomic adj layer adj (deposit\$3 or epitax\$6))) and ((deposit\$3 or decompos\$5 or condens\$5 or contaminat\$4 or coat\$3) near3 (minimiz\$5 or eliminat\$3 or prevent\$3 or avoid\$5) with (chamber or vessel or reactor or wall) with (heat\$3 or cool\$3 or temperature)))	US-PGPUB; USPAT	OR	ON	2005/02/24 10:22

L17	8	L8 and ((ALE or ALD or (atomic adj layer adj (deposit\$3 or epitax\$5)))) and ((independent\$6 or separat\$5 or separat\$5 or individual\$6) with (control\$5 or monitor\$5 or regulat\$6 or adjust\$5 or manipul\$6) with (heat\$5 or temperature) with (substrate or wafer or base or support or susceptor or pedestal) with (chamber or wall or reactor or sidewall or vessell or vessel))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/02/24 10:33
L18	15	((ALE or ALD or (atomic adj layer adj (deposit\$3 or epitax\$5)))) and ((independent\$6 or separat\$5 or separat\$5 or individual\$6) with (control\$5 or monitor\$5 or regulat\$6 or adjust\$5 or manipul\$6) with (heat\$5 or temperature) with (substrate or wafer or base or support or susceptor or pedestal) with (chamber or wall or reactor or sidewall or vessell or vessel))	US-PGPUB; USPAT	OR	ON	2005/02/24 10:32
L19	7	L18 not L17	US-PGPUB; USPAT	OR	ON	2005/02/24 10:31
L20	3	((ALE or ALD or (atomic adj layer adj (deposit\$3 or epitax\$5)))) and ((independent\$6 or separat\$5 or separat\$5 or individual\$6) with (control\$5 or monitor\$5 or regulat\$6 or adjust\$5 or manipul\$6) with (heat\$5 or temperature) with (substrate or wafer or base or support or susceptor or pedestal) with (chamber or wall or reactor or sidewall or vessell or vessel))	EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/02/24 10:32
L21	18	L8 and (((ALE or ALD or (atomic adj layer adj (deposit\$3 or epitax\$5)))) with (temperature near2 window))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/02/24 10:38
L22	51	((ALE or ALD or (atomic adj layer adj (deposit\$3 or epitax\$5)))) with (temperature near2 window))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/02/24 10:41
L23	33	L22 not L21	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/02/24 10:38

L24	1	((((ALE or ALD or (atomic adj layer adj (deposit\$3 or epitax\$5)))) with (window) with (wall or sidewall)))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/02/24 11:46
L25	33	((((ALE or ALD or (atomic adj layer adj (deposit\$3 or epitax\$5)))) with (temperature or heat\$5) with (wall or sidewall)))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/02/24 10:47
L26	32	L25 not L24	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/02/24 10:43
L27	481	((ALE or ALD or (atomic adj layer adj (deposit\$3 or epitax\$5)))) same ((grow\$5 or deposit\$5 or ALD or ALE or film or layer or monolayer) with (wall or sidewall))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/02/24 10:48
L28	484	((ALE or ALD or (atomic adj layer adj (deposit\$3 or epitax\$5)))) same ((grow\$5 or deposit\$5 or ALD or ALE or film or layer or monolayer or coat\$5 or passivat\$5) with (wall or sidewall))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/02/24 10:55
L29	74	L28 and L8	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/02/24 10:49
L30	179	((ALE or ALD or (atomic adj layer adj (deposit\$3 or epitax\$5)))) and ((grow\$5 or deposit\$5 or ALD or ALE or film or layer or monolayer or coat\$5 or passivat\$5) with (wall or sidewall or chamber or reactor or vessel or vessell) with (rate or spee) with (substrate or wafer or base or workpiece or (work adj piece)))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/02/24 11:02
L31	80	((ALE or ALD or (atomic adj layer adj (deposit\$3 or epitax\$5)))) same ((grow\$5 or deposit\$5 or ALD or ALE or film or layer or monolayer or coat\$5 or passivat\$5) with (wall or sidewall or chamber or reactor or vessel or vessell) with (rate or speed or rapid\$3) with (substrate or wafer or base or workpiece or (work adj piece)))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/02/24 11:00

L32	5	((ALE or ALD or (atomic adj layer adj (deposit\$3 or epitax\$5)))) same ((grow\$5 or deposit\$5 or ALD or ALE or film or layer or monolayer or coat\$5 or passivat\$5) with (wall or sidewall) with (rate or speed or rapid\$3) with (substrate or wafer or base or workpiece or (work adj piece)))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/02/24 11:00
L33	92	((ALE or ALD or (atomic adj layer adj (deposit\$3 or epitax\$5)))) and ((grow\$5 or deposit\$5 or ALD or ALE or film or layer or monolayer or coat\$5 or passivat\$5) near3 (rate or speed\$3 or rapid\$5) with (wall or sidewall or chamber or reactor or vessel or vessell) with (substrate or wafer or base or workpiece or (work adj piece)))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/02/24 11:11
L34	36	L33 and L8	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/02/24 11:03
L35	56	L33 not L34	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/02/24 11:06
L36	90	((ALE or ALD or (atomic adj layer adj (deposit\$3 or epitax\$5)))) and ((grow\$5 or deposit\$5 or ALD or ALE or film or layer or monolayer or coat\$5 or passivat\$5) near4 (fast\$4 or slow\$5 or quick\$3 or high\$3 or low\$3) with (wall or sidewall) with (substrate or wafer or base or workpiece or (work adj piece)))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/02/24 11:16
L37	6	L36 and L8	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/02/24 11:14
L38	84	L36 not L37	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/02/24 11:14
L39	16	((ALE or ALD or (atomic adj layer adj (deposit\$3 or epitax\$5)))) near3 (chamber or reactor or vessel or vessell) near2 (wall or sidewall)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/02/24 11:18

L40	102	((ALE or ALD or (atomic adj layer adj (deposit\$3 or epitax\$5)))) with (rate or speed or fast\$4 or slow\$4 or increas\$4 or decreas\$5 or high\$4 or low\$4) with (depend\$5 or determin\$5 or optimiz\$6 or influenc\$5 or control\$6 or regulat\$5) with (heat\$4 or temperature)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/02/24 11:20
L41	31	L40 and L8	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/02/24 11:34
L42	71	L40 not L41	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/02/24 11:39
L43	1	((ALE or ALD or (atomic adj layer adj (deposit\$3 or epitax\$5)))) and ((wall or sidewall) near2 temperature with (higher or lower or increas\$5 or reduc\$5) with temperature near2 (substrate or wafer or support or pedestal or susceptor or workpiece or base or (work adj piece)))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/02/24 11:47
L44	1	((ALE or ALD or (atomic adj layer adj (deposit\$3 or epitax\$5)))) and ((wall or sidewall) near2 temperature with (higher or lower or increas\$5 or reduc\$5 or decreas\$5 or different\$2) with temperature near2 (substrate or wafer or support or pedestal or susceptor or workpiece or base or (work adj piece)))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/02/24 11:49
L45	8	((ALE or ALD or (atomic adj layer adj (deposit\$3 or epitax\$5)))) and ((wall or sidewall) with (hotter or cooler or colder) with (substrate or wafer or support or pedestal or susceptor or workpiece or base or (work adj piece)))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/02/24 11:50
L46	0	((ALE or ALD or (atomic adj layer adj (deposit\$3 or epitax\$5)))) same (nest\$5 near3 window)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/02/24 11:51

L47	0	((((ALE or ALD or (atomic adj layer adj (deposit\$3 or epitax\$5)))))) same (nest\$5 near3 temperature)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/02/24 11:51
L48	0	((((ALE or ALD or (atomic adj layer adj (deposit\$3 or epitax\$5)))))) and (nest\$5 near3 (window or temperature))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/02/24 11:51
L49	17	((((ALE or ALD or (atomic adj layer adj (deposit\$3 or epitax\$5)))))) and ((temperature) near3 (window or range) with (increas\$4 or decreas\$4 or high\$4 or low\$4 or reduc\$5 or influenc\$5 or control\$6 or optimiz\$6 or regulat\$6) with (rate or speed) with (ALD or ALE or deposit\$4 or coat\$5 or monolayer or adsorp\$6 or chemisor\$8 or physisor\$8))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/02/24 11:54
L50	6	L49 and L8	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/02/24 11:57
L51	11	L49 not L50	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/02/24 12:07
L52	2	"6015590".pn.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/02/24 12:07